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Tokyo Electron Limited Begins Marketing, Sales and Support for New Generation Ion Implantation Systems from AIBT Inc.

Tokyo, Japan – February 25, 2004

TOKYO, JAPAN - Tokyo Electron Limited (TEL; Head Office: Minato-ku, Tokyo; President & CEO: Kiyoshi Sato), will sign a sales representative contract with Advanced Beam Technology, Inc. (AIBT; Head Office: San Jose, CA; President & CEO: Daniel Tang), and will begin to undertake marketing, sales and support for the ion implantation system from AIBT Inc. in Japan, US, Korea and Europe.

“Tokyo Electron will provide a powerful global sales and service engine to market AIBT’s new-generation technology of high current ion implantation,” said Daniel Tang, CEO and president of AIBT, “This sales representation agreement with one of the world’s largest semiconductor equipment supplier establishes AIBT as an unstoppable new market force for high current implanter.”

To meet requirements of leading edge technologies, shrinking devices require more precision for dosage and energy purity control for ion implantation processes. Approaching 90nm and beyond, high current with extreme low energy beam is of crucial importance to achieve next generation’s production needs. High tilt angle for HALO/pocket implantation is another emerging challenge.

“We are very pleased to offer AIBT’s enabling ion implant technology and product to our customers utilizing our world-wide support network,” said Ken Sato, CEO, President of TEL.

TEL is beginning the distribution of AIBT’s iStar, a new generation ion implanter.

The iStar is a low energy, high current batch mode ion implanter most suitable for USJ formation for advanced technology nodes. Its unique tall beam design can achieve high beam current at low energy level. Combined with high mechanical wafer handling speed, iStar can achieve high productivity for advanced technology. A special design in the beam line enables iStar to achieve high energy purity of greater than 99.9%. Rotatable wafer pad design is used for the thirteen wafers spoke so that the system can perform tilt angle implant up to +/- 45 degree. iStar can meet both conventional and upcoming requirements of advanced wafer fabrication. It will reduce cost of ownership by both reducing capital and operating expenses.

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About AIBT

Established in 1999, AIBT was funded and led by Hemes-Epitek Corp. (HE; Head Office: Hsin-Chu, Taiwan Chairman & CEO Archie Hwang), which has a long relationship and mutual trust with TEL. With its home base in Silicon Valley, AIBT's key focus for the past few years has been devoted to develop a new generation of high current ion implanter - iStar. The company is currently pilot testing iStar at customer and investor sites. <http://www.aibt-inc.com>

About TEL

Tokyo Electron Limited, established in 1963, is a leading supplier of innovative semiconductor and LCD production equipment worldwide. Product lines include coater/developers, oxidation/diffusion furnaces, dry etchers, CVD systems, sputtering systems (PVD), wet chemical stations and test systems. In Japan, TEL distributes other leading edge semiconductor equipment tools, such as metrology tools or process control systems. In addition, TEL distributes high quality computer systems, semiconductor devices and electronic components of other leading suppliers, as well as computer network related products from around the world.

To support this diverse product base, TEL has strategically established research & development, manufacturing, sales and service locations all over the world. TEL estimates in the current fiscal year that revenues will exceed 800 billion yen, or more than 7 billion dollars. TEL is a publicly held company listed on the Tokyo Stock Exchange. <http://www.tel.co.jp>

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